

(22)

2-20

REDACTED

TDG PATENT HARVESTING SESSION
GROUP 2—ROOM C-2
Technical Leader: Chris Lyons
TOPIC: Advanced Patterning Modules

REDACTED

AMD INVENTION DISCLOSURETLD ID# REDACTED

REDACTED

Sunnyvale x42110, return to MS68,

Texas x55964 return to MS562

REDACTED

Project: Product: Process: Technology to which the invention applies (*identify*):

List 2 to 5 key words useful to search by to find patents or art related to this invention:

Working title of invention: Dual mask to change bus for printing main contacts
or vias

INVENTOR/SESSION PARTICIPANT ADDRESS INFORMATION IS ON THE NEXT PAGE (IA)

Inventor's signature : _____ date : _____

Inventor's printed full name: RG + all + U30 .0 + Hung E. Kim Citizenship: _____

Employee #: _____ Extension: _____ Mail stop: _____ Home telephone: () _____

Division: _____ Directorate: _____ Dept #: _____ Dept : _____ Manager: _____

Residence address: _____

Post Office address: _____

Co-Inventor's signature : _____ date : _____

Co-Inventor's printed full name: _____ Citizenship: _____

Employee #: _____ Extension: _____ Mail stop: _____ Home telephone: () _____

Division: _____ Directorate: _____ Dept #: _____ Dept : _____ Manager: _____

Residence address: _____

Post Office address: _____

Co-Inventor's signature : _____ date : _____

Co-Inventor's printed full name: _____ Citizenship: _____

Employee #: _____ Extension: _____ Mail stop: _____ Home telephone: () _____

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Co-Inventor's signature : _____ date : _____

Co-Inventor's printed full name: _____ Citizenship: _____

Employee #: _____ Extension: _____ Mail stop: _____ Home telephone: () _____

Division: _____ Directorate: _____ Dept #: _____ Dept : _____ Manager: _____

Residence address: _____

Post Office address: _____

List on additional sheet if there are more co-inventors and list total number of inventors here: _____

Name(s) of attorney(s) preferred by inventor(s) to prepare patent application, if known:

LAW FIRM: FOLEY & LARDNER
ATTORNEYS: PHIL ARTICOLA and TOM BILODEAU

Witness 1 initial: _____ Witness 2 initial: _____

AMD INVENTION DISCLOSURE

California x42110, return to MS68,

Texas x55964 return to MS562,

Dresden x83401 Silke Kretzschmar at MS E21-PP.

TLD ID# _____

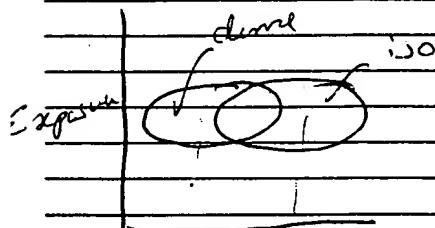
Rec'd date _____

State the problem solved by this invention: _____

Brief description and/or sketch of invention (please attach copies of AMD patent notebook pages, reports or drawings):

As contact size shrinks the experimental data shows that

the lens don't focus for printing dense & isolated vias at different



→ Proposal is to use 2 masks to print the
2 types of vias separately ~~with~~ a ~~in~~ size

2 ~~types~~ different focus settings to get
best focus.

- Broad claim is as we have many pitches
we may use many masks with different
optical settings to get best print resolution
include illuminator, focus, NA, Sigma etc.

Patent notebook # _____ Page numbers _____ Number of drawings _____

Witness 1 initial: _____ Witness 2 initial: _____